

Title (en)
DEVICE AND PROCESS FOR REMOVING MICROBIAL IMPURITIES IN WATER BASED LIQUIDS AS WELL AS THE USE OF THE DEVICE

Title (de)
VORRICHTUNG UND VERFAHREN ZUR ENTFERNUNG VON MIKROBIELLEN VERUNREINIGUNGEN IN FLÜSSIGKEITEN AUF WASSERBASIS SOWIE VERWENDUNG DER VORRICHTUNG

Title (fr)
DISPOSITIF ET PROCÉDÉ D'ÉLIMINATION D'IMPURETÉS MICROBIENNES DANS DES LIQUIDES À BASE D'EAU AINSI QU'UTILISATION DU DISPOSITIF

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Application
EP 09776204 A 20090930

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Abstract (en)
[origin: WO2010037391A1] The present invention relates to the technical field of electrochemical elimination or reduction of microbial impurities of liquids. The liquids treated may inter alia include wastewater, industrial process water and water intended for human consumption. The device comprises a disinfection chamber connected through a liquid inlet located in the bottom of a base area by a manifold; an inner chamber housing an electrode stack comprising at least two perforated electrode plates made of conductive material symmetrically placed at a distance of 1-5 mm connected in parallel via connector mounted at the chamber; said electrode plates being separated from each other and the chamber wall at a fixed distance by spacers, and arranged such that in perpendicular plane view 60 -100 % of the area of passage is covered by the electrodes; an outer chamber; an outer shell; a liquid outlet; connectors for wiring connecting the connector and one or more external power supply units,- each of the above elements being designed such that said liquid has a forward velocity of 2 - 50 cm/ s and an initial perpendicular velocity component above 10 cm/s and wherein further the current density is above 5 mA/ cm².

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Citation (search report)
See references of WO 2010037391A1

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